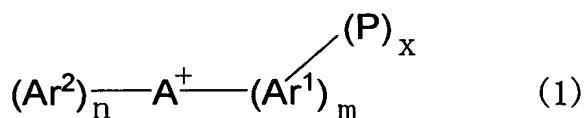


ABSTRACT OF THE DISCLOSURE

An onium salt compound having a cation moiety of the following formula (1) is disclosed.



wherein A represents I or S, m is 1 or 2, n is 0 or 1, x is 1-10, and Ar¹ and Ar² are (substituted) aromatic hydrocarbon group, and P represents -O-SO₂R, -O-S(O)R, or -SO₂R, wherein R represents a hydrogen atom, a (substituted) alkyl group, or a (substituted) alicyclic hydrocarbon group. The onium salt compound is suitable as a photoacid generator for photoresists of a positive-tone radiation-sensitive resin composition. The positive-tone radiation-sensitive resin composition containing this compound is useful as a chemically-amplified photoresist exhibiting high resolution at high sensitivity, responsive to various radiations, and having outstanding storage stability.